

525
A1 > ABSTRACT

A method for creating dummy fill metal patterns (10) in a reflective LCOS array (11) in order to minimize distortion in images reflected from mirrors (14) thereof . A metal fill pattern (50) is selected from an area near a functional circuitry (32) pattern. The functional circuitry (32) pattern is grown to create a margin area (34) leaving a fill area (38) to be filled. The metal fill pattern (50) is trimmed to the outline of the fill area (38). Metal sliver(s) (66) or other such artifacts are removed to conform to design specifications, thereby creating a second trimmed metal traces (74) pattern. The second fill metal traces (74) are combined with the functional circuitry (32) traces to form a completed metal trace pattern (76) in an overlay functional and dummy patterns operation (78).